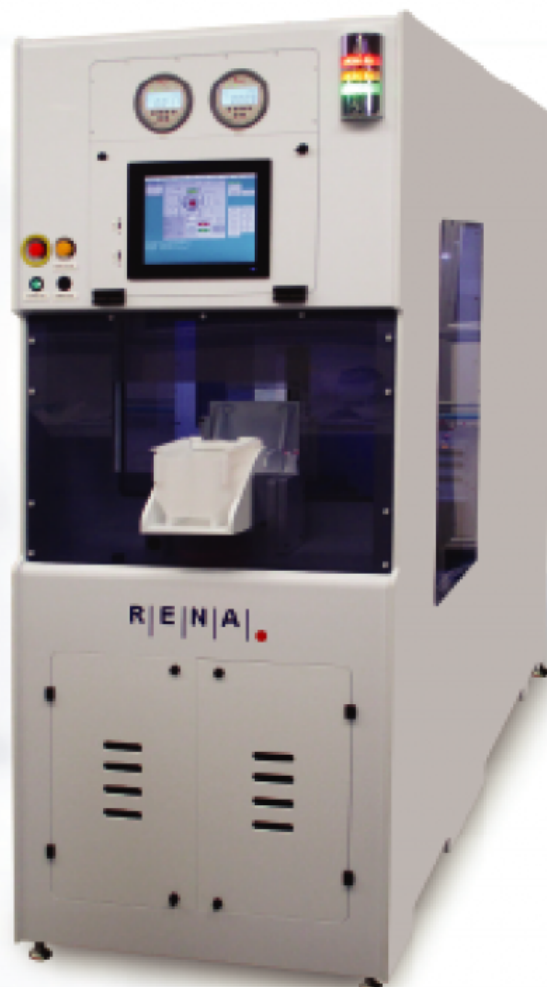


MEI/RENA North America Announces the Release of the Inception Single Wafer Processing Tool

Clean, Etch, Strip & Dry - Enabling the Transition from R&D to Pilot Production



Albany, Jun 16, 2020 ([Issuewire.com](https://www.issuewire.com)) - MEI Wet Processing Systems and Services, now a member of RENA Group, has added to our portfolio of Wet Processing Platforms. Known for proven Immersion and Batch Spray Technology, we are proud to announce the addition of a Single Wafer Platform called the *Inception*.

The Inception enables transition from R&D to Pilot line production, and is capable of all wet processes - Clean, Etch, Strip and Dry.

MEI/RENA Technologies North America has just shipped an *Inception* Single Wafer Tool to a major Compound Semiconductor customer who will utilize its capabilities in an Acid Clean Process.

Ed Jean, CEO of MEI/RENA Technologies North America says, “if all you have is a hammer, everything looks like a nail, Batch Immersion, Batch Spray, and Single Wafer Tools all have their place in the wet process world. Most equipment suppliers however offer a one-size-fits-all approach, trying to “hammer” your application into the only platform they offer. With the addition of the Inception Single Wafer Tool to our product lineup, RENA provides the appropriate Platform for any Wet Clean, Etch, or Strip application.”

Heath Phillips, MEI/RENA Technologies NA Spray Product Manager says, “The *Inception* Single Wafer platform provides our customers, who perform tests in beakers and pie plates, the consistency to develop a POR and automate their process.”

Features of the *Inception* Single Wafer Tool:

- FEOl (Acid) & BEOl (Solvent) processing applications
- Automated Wafer Handling (Manual Load Optional)
- Wafers up to 200mm and masks up to 7 x 7
- Dual moving spray arms with separate chem lines
- Stationary bottom spray nozzles for DI and N2
- Etch uniformity exceeds batch systems
- Stationary bottom spray nozzles for DI and N2
- Standard dual tank design provides multi-step processing (4-tank optional)
- Manual or automated wafer handling
- Single or dual load ports
- Low utilities consumption
- Small Footprint Dimensions - 36"w x 83"h x 76"l
- Highly flexible software enables rapid process development

About MEI/ RENA Technologies NA

MEI/RENA Technologies NA handles a wide range of wet processes, including clean, etch, strip & plating. Platforms for pilot line production to High volume production. **MEI Wet Processing Systems and Services LLC** of Albany, Oregon, is a wet processing equipment and services company serving the Semiconductor, MEMs, Solar, and high technology industries. MEI's specialties include patented solutions for wet processing applications, including [Metal Lift-off](#), [Advanced Wafer Etching](#), [Wafer Stripping](#), and [Wafer Cleaning](#) solutions. Exceptional process control is provided through MEI's proprietary [IDX Flexware Process Control Software](#). Providing award-winning service and support since 1990, MEI has a commitment to outstanding customer service and its products. MEI Wet Processing has sales offices in the United States, Europe, China, Asia, and the Middle-East. For more information, please visit www.meillc.com.

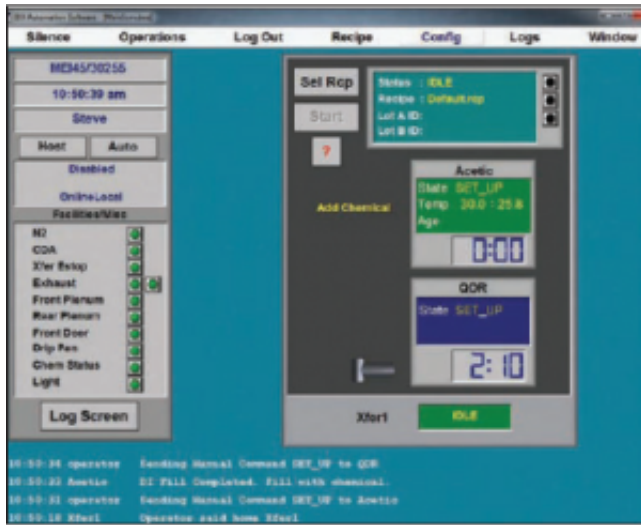
MEI Wet Processing's goal is to provide our customers with the best possible process control by using state-of-the-art technology to ensure maximum performance, uptime, and reliability. Through a combination of patented technology, process experience, software sophistication, and robust design, MEI provides superior wet process systems for a wide variety of applications.

CONTACTS

For Sales:

Heath Phillips
heath.phillips@RENA.com
(541) 917-3626

www.renatechna.com



idx
Flexware
PROCESS CONTROL SOFTWARE

Media Contact

MEI Wet Processing, Heath Phillips

heath.phillips@rena.com

(541) 917-3626

3838 Western Way NE

Source : MEI/RENA Technologies NA

[See on IssueWire](#)